

Effect of lattice strain on X-ray Diffraction, Raman Spectroscopy and Optical Properties of as Synthesis Nanocomposite ZnO-SnO₂-TiO₂ Thin Film by Spray Pyrolysis Method

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ABSTRACT

The nanocomposite ZnO-SnO₂-TiO₂ thin films were synthesized via spray pyrolysis method. They were studied by X-ray diffraction (XRD) and Raman spectroscopy in order to determinate a film composition and structural properties. The effect of annealing temperatures on the crystalline structure and optical property was investigated. The surface morphologies of the thin films were studied by using atomic force microscopy (AFM). At low annealing temperature (700 °C) thin film shows amorphous in nature. The crystallinity of thin film was achieved at annealing temperature ≥ 750 °C. The broadening of XRD and Raman peaks are mainly due to the lattice strain present in the nanocomposite thin films which results the decreased in intensity of the peaks. An AFM image shows that the grains are nearly in spherical shape and they increases with annealing temperature. The optical band gaps of thin films were calculated by using UV-Vis. Spectroscopy and found 3.68 eV, 3.70 eV, 3.74 eV and 3.76 eV at annealing temperature 700 °C, 750 °C, 850 °C and 900 °C respectively.

Keywords:-Nanocomposite ZnO-SnO₂-TiO₂ Thin Film, XRD, W-H Plot, Raman, AFM, Lattice Strain.

1. Introduction

Thin films of nanocomposite considered at least two phases, an amorphous phase and nanocrystalline phase, or a nanocrystalline phase with another nanocrystalline phase. Due to the unique physical-chemical properties [1-2], structural [3] and optical [4] the nanocomposite films have received much attention recently. To synthesis of nanocomposite thin films many factors are necessary for considerations during synthesis such as surface and interfacial energy, the interface volume, crystallite size, epitaxial stress and strain, texture etc. The metal oxides such as ZnO, SnO₂, TiO₂, CuO, WO₃ etc. are very important for technologically as well as fundamental point of view. The Synthesis and fabrication of nanocomposite thin films based on semiconducting oxides is an important goal for the obtainment of improved functional performances in advanced fields such as sensing, optoelectronics, and catalysis. Recently, the fabrication of materials showing novel technological applications mixed metal oxides or binary semiconducting systems have attracted more and more attention have been prepared and some researchers pointed out that they were promising candidates for electronic instruments. To enhance the mechanical and photocatalytic property of TiO₂ many researchers have been prepared composites with TiO₂ for example ZnO-TiO₂ [5], SnO₂-TiO₂ [6] etc. The coupled oxide semiconductor shows efficient charge separation which suppress the charge recombination in nanoporous dye sensitized photoelectrochemical (DSPE) solar cells, nanocrystalline coupled semiconductor electrodes of the type OTE/SnO₂/TiO₂ have been prepared[7]. The composite SnO₂/TiO₂/SnO₂ system has a higher surface energy than the individual SnO₂ and TiO₂ oxides whereas for the TiO₂/SnO₂/TiO₂ the corresponding values are of the same order that of TiO₂ oxide and lower than those of SnO₂ oxide has been calculated theoretically by using density functional theory [8].

To the best of our knowledge, there are no reports on the synthesis of composite ZnO-SnO₂-TiO₂ thin film. In this study, ZnO-SnO₂-TiO₂ nanocomposite thin films were synthesized by a Spray pyrolysis method and were characterized using X-ray diffractometer (XRD), micro Raman spectrometer, UV-Vis.-NIR spectroscopy and atomic force microscope (AFM).

2. Experimental details

The number of thin film nanocomposite of ZnO, SnO₂, and TiO₂ of energy band gaps of 3.4 eV, 3.6 eV and 3.2 eV respectively were synthesized by spray pyrolysis method. Zinc acetate dihydrate Zn(CH₃COO)₂.2H₂O (Merck, India), tin chloride dihydrate SnCl₂.2H₂O (Merck, India) and titanium tetra chloride TiCl₄ (Merck, India) were used as precursor and ethanol (C₂H₅OH) and hydrochloric acid (HCl) were used as solvent.

4.3898gm of Zn(CH₃COO)₂.2H₂O (1M) was dissolved in mixture of 16ml ethanol+4ml HCl, and stirred at room temperature for 6 h. The transparent solution of [Zn(CH₃COO)₂+C₂H₅OH+HCl] was obtained; 4.5126gm of SnCl₂.2H₂O (1M) was dissolved in mixture of 16ml ethanol+4ml HCl, and stirred at room temperature for 6 h. The transparent solution of [SnCl₂+C₂H₅OH+ HCl] was obtained; 2.2ml of TiCl₄(1M) was dissolved in mixture of 16ml ethanol+4ml HCl, and stirred at 80 °C temperature for 6 h. The transparent solution of [TiCl₄+ C₂H₅OH +HCl] was obtained.

Now solutions [Zn(CH₃COO)₂+ C₂H₅OH+ HCl],[SnCl₂+C₂H₅OH+ HCl] and [TiCl₄+ C₂H₅OH +HCl] were mixed together, and stirred at room temperature for 10 h to get the homogenous transparent solution. The homogenous solution were sprayed on glass substrates at 400 °C. The deposited films were annealed at 700 °C, 750 °C, 800 °C, 850 °C and 900 °C for 30 minutes for crystallinity. Film deposition process by spray pyrolysis method was summarised as in fig. 1: The X-ray diffraction pattern was recorded by using powder X-ray diffractometer (Bruker D8 Advance) at room temperature with monochromatic CuK_α radiation ($\lambda=1.5406 \text{ \AA}$) in a wide range of Bragg angle 2θ from 20° to 70° with scanning rate of 0.5° min⁻¹. The Raman spectra were recorded by using Micro Raman spectrometer (JobinYvonHoribra LABRAM-HR) at room temperature in the range of wave-number from 100 cm⁻¹ to 1300 cm⁻¹. The surface morphology and roughness of nanocomposite thin films were carried out with the help of Atomic Force Microscope (AFM) (SPM Digital Instrument NanoscopeIIIa), the absorptions spectra were recorded by using UV-Vis.-NIR spectrophotometer (Perkin Elmer, USA. Model: Lambda 950) in the wavelength range 200-858nm.

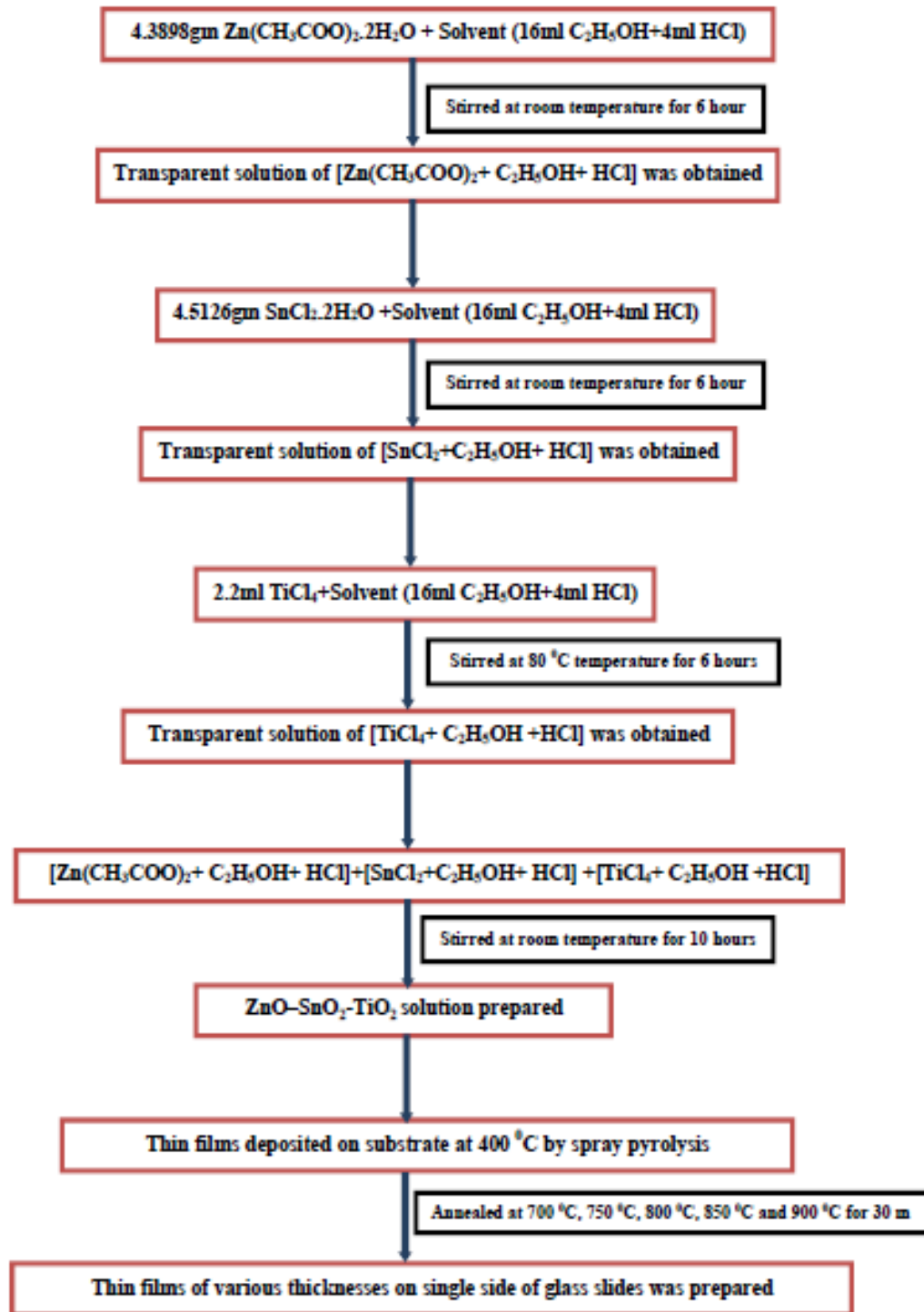


Figure 1: Flow chart of synthesis of nanocomposite ZnO-SnO₂-TiO₂ thin film by spray pyrolysis method .

3. Results and Discussion

3.1 X-Ray Diffraction Analysis

XRD was employed to determine the phase analysis of each thin film annealed at increasing temperatures as shown in fig. 2. It can be seen that the film is amorphous annealed at 700 °C. When the temperature increased to 750 °C, as shown in fig. 2 seven diffraction peaks are found, which belong to (110), (221), (220) tetragonal rutile phase of TiO₂ with space group P4₂/mnm (JCPDS No. 21-1276), (221) orthorhombic brookite phase of TiO₂ with space group Pcab (JCPDS No. 29-1360), (101) tetragonal rutile phase of SnO with space group P4/nmm (JCPDS No. 06-0395), (310) tetragonal rutile phase of SnO₂ with space group P4₂/mnm (JCPDS No. 01-077-0449) and (002) hexagonal wurtzite phase of ZnO with space group P6₃mc (JCPDS No. 89-1397). Further, as annealing temperature was increased (221) diffraction peak disappeared at 800 °C, 850 °C and 900 °C respectively. At annealing temperature 900 °C the intensity of the (310) diffraction peak was almost zero. The above XRD results show that the structure of the thin films changed from amorphous to crystalline phase with the increasing of the annealing temperature. The Crystallite size and the lattice strain were determined for each crystalline thin film by adopting the Williamson-Hall (W-H) equation [9].

$$\beta \cos \theta = \frac{0.9\lambda}{D} + 4\varepsilon \sin \theta \quad (1)$$

In equation 1, λ is the wavelength of X-ray radiation, β is the full width at half maximum (FWHM) and θ is the diffraction angle of the diffraction peaks. D is the effective crystallite size with lattice strain, and ε is the effective value of lattice strain. $\beta \cos \theta$ is plotted against $4 \sin \theta$, and after linear fitting, the intercept gives the value of D and the slope gives the value of ε . Fig. 3(a), 3(b), 3(c) and 3(d) illustrates the W-H plot of all the crystalline nanocomposite ZnO-SnO₂-TiO₂ thin films. The value of crystallite size and of lattice strain of each crystalline thin film is inserted in Table 1. As evident from Table 1, film annealed at 800 °C exhibits the highest lattice strain, whereas film annealed at 900 °C has the lowest. Positive strain shows the system is under tensile strain while negative strain compressive strain. As the temperature increases the crystallite size also increases due to the increase in thermal energy which confirms from Table 1. There is a nonuniform strain developed in the thin film because their strain value does not show regular

variation with the annealing temperature. Due to nonuniform strain the shape of the peak will change and peak will become broaden and the resultant intensity will decrease. This is the

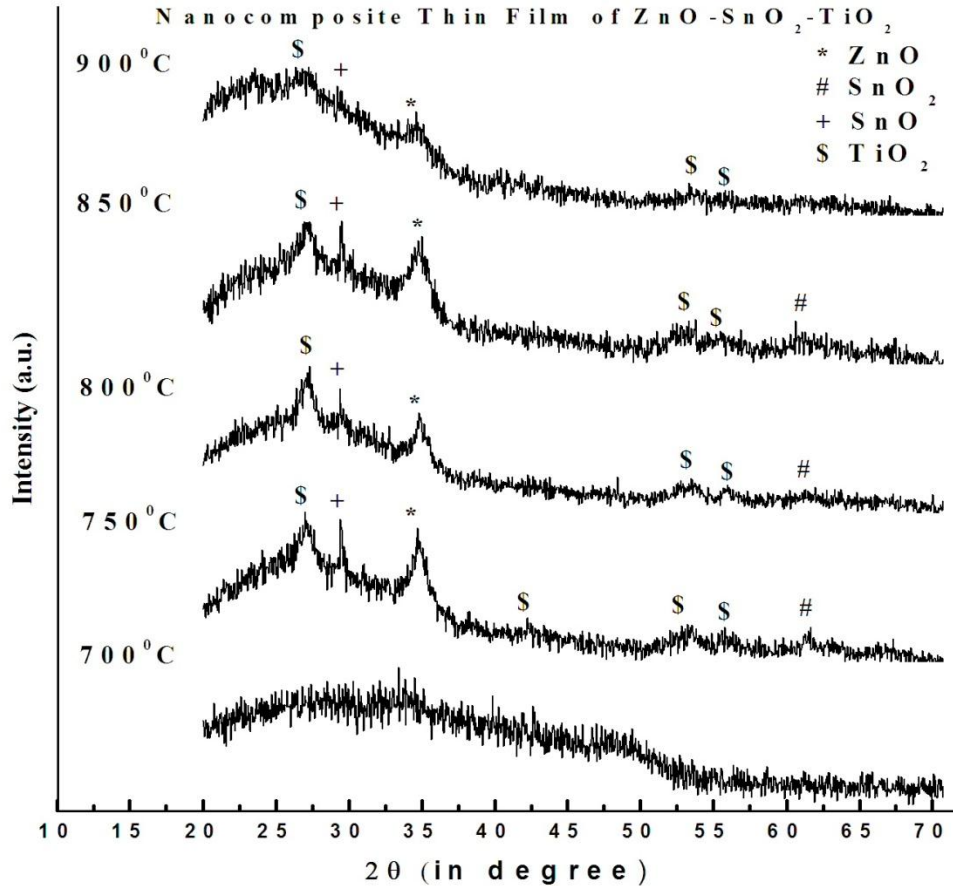


Figure 2: XRD of the nanocomposite ZnO-SnO₂-TiO₂ annealed at 700 °C, 750 °C, 800 °C, 850 °C and 900 °C temperature.

main reason that (221) and (310) diffraction peaks intensity becomes zero and finally disappeared at annealing temperature 900 °C also the intensity decreases of the diffraction peaks (110), (101), (221) and (220) with the annealing temperature as show in fig. 2. The mechanism of broadening of the X-ray diffraction peak due to strain is illustrated in fig. 4. If there is no strain in a portion of the grain, the spacing between the planes everywhere is same and equilibrium spacing is d . The diffraction on line from these planes appear on the right as shown in fig. 4(a). If the uniform tensile strain is applied at right angles to the reflecting planes, their spacing becomes larger than d , and the corresponding diffraction line shifts to lower angles without any

change in shape and size as shown in fig. 4(b). However the behavior of the diffraction peak is totally different when the nonuniform strain is applied to the reflecting planes. The grain is bent in presence of nonuniform strain, on the top (tension) side the plane spacing exceeds d , on the

Table 1 Crystallite size, lattice strain, particle size and roughness of the nanocomposite ZnO- SnO₂- TiO₂ thin films

Annealing Temperature (°C)	Crystallite Size (nm)	Lattice Strain (ϵ)	Particle Size (nm)	Roughness (nm)
700	-	-	68	1.67
750	11	0.00341	74	1.22
800	27	0.01738	-	-
850	30	0.01702	109	1.78
900	34	-0.01631	-	9.81

bottom (compression) it is less than d , and somewhere in between it equals d . We may imagine this grain to be composed of a number of small regions in each of which the plane spacing is substantially constant but different from the spacing in adjoining regions. These regions cause the various sharp diffraction lines indicated on fig. 4(c) within the broad peak. The sum of these sharp lines, each slightly displaced from the other, is the broadened diffraction line shown by curve in fig. 4(c) [10].

3.2. Raman Spectroscopy Analysis

Raman spectroscopy was employed to phase identification of the as synthesized nanocomposite ZnO-SnO₂-TiO₂ thin film by spray pyrolysis method. The Raman spectra of the annealed nanocomposite thin films at increasing temperature along with their modes of the nanocomposite are shown in fig. 5. At annealing temperature 700 °C and 800 °C two Raman peaks at wavenumber 564 cm⁻¹ and 1098 cm⁻¹ are observed which belong to vibrational mode A₁(LO) and 2LO of hexagonal wurtzite ZnO [11] phase also one Raman peak at wavenumber 660 cm⁻¹ assigned vibrational mode E_g of tetragonal anatase phase [12] at 800 °C. The above result indicates that at annealing temperature 700 °C the formation of nanocomposite was not

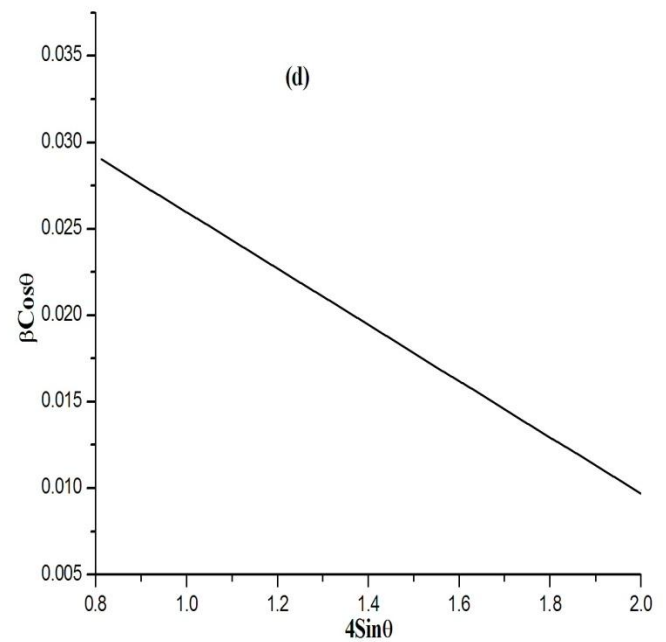
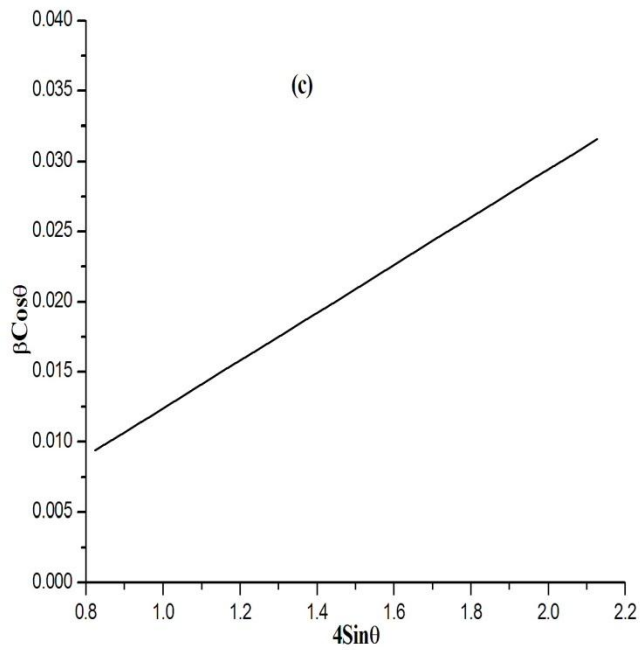
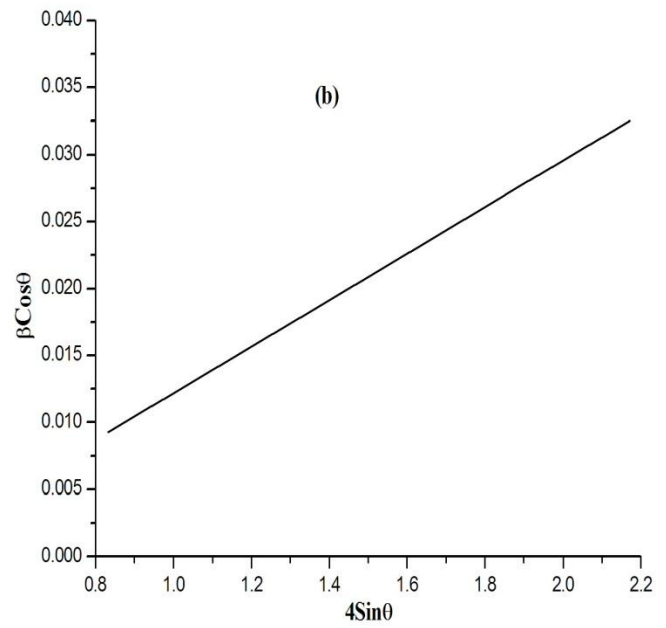
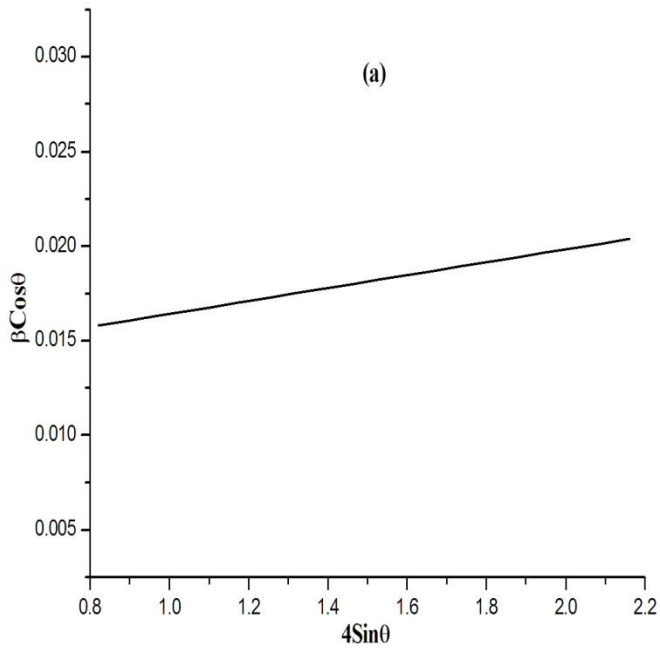


Figure 3: W-H plot of nanocomposite ZnO-SnO₂-TiO₂ thin film annealed at (a) 750 °C, (b) 800 °C, (c) 850 °C and (d) 900 °C.

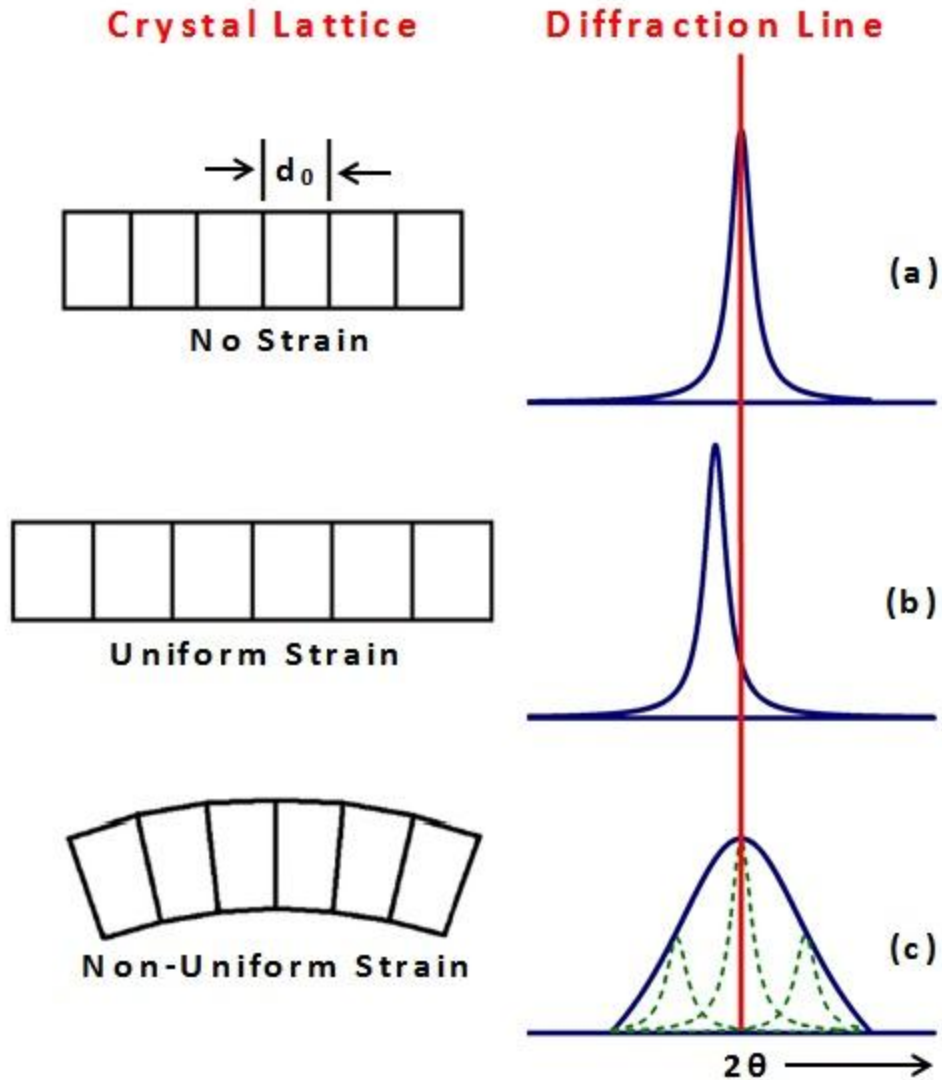


Figure 4: Effect of Lattice strain on X-ray Diffraction Line

At annealing temperature $750\text{ }^{\circ}\text{C}$ eleven Raman peaks are observed, in which out of two Raman peak at wavenumber 117 cm^{-1} and 151 cm^{-1} belong to the vibrational mode E_g and A_{1g} of a brookite TiO_2 phase [13-14], two Raman peak at wavenumber 235 cm^{-1} and 316 cm^{-1} belong to vibrational mode B_{1g} and one at wavenumber 615 cm^{-1} belong to vibrational mode A_{1g} of rutile TiO_2 phase[13], two Raman peak of vibrational mode B_{2g} at wavenumbers 276 cm^{-1} and 784 cm^{-1} and one Raman peak at wavenumber 713 cm^{-1} of vibrational mode $E_u(\text{LO})$ belong to tetragonal SnO_2 phase [15] and remaining three Raman peaks at wavenumber 435 cm^{-1} , 671 cm^{-1} and 1095 cm^{-1} belong to vibrational mode E_2^{high} , TA+LO and 2LO hexagonal wurtzite ZnO

phase [11, 16]. As from above results, clears the formation of nanocomposite ZnO-SnO₂-TiO₂ thin film as revealed by the presence of ZnO, SnO₂ and TiO₂ phase.

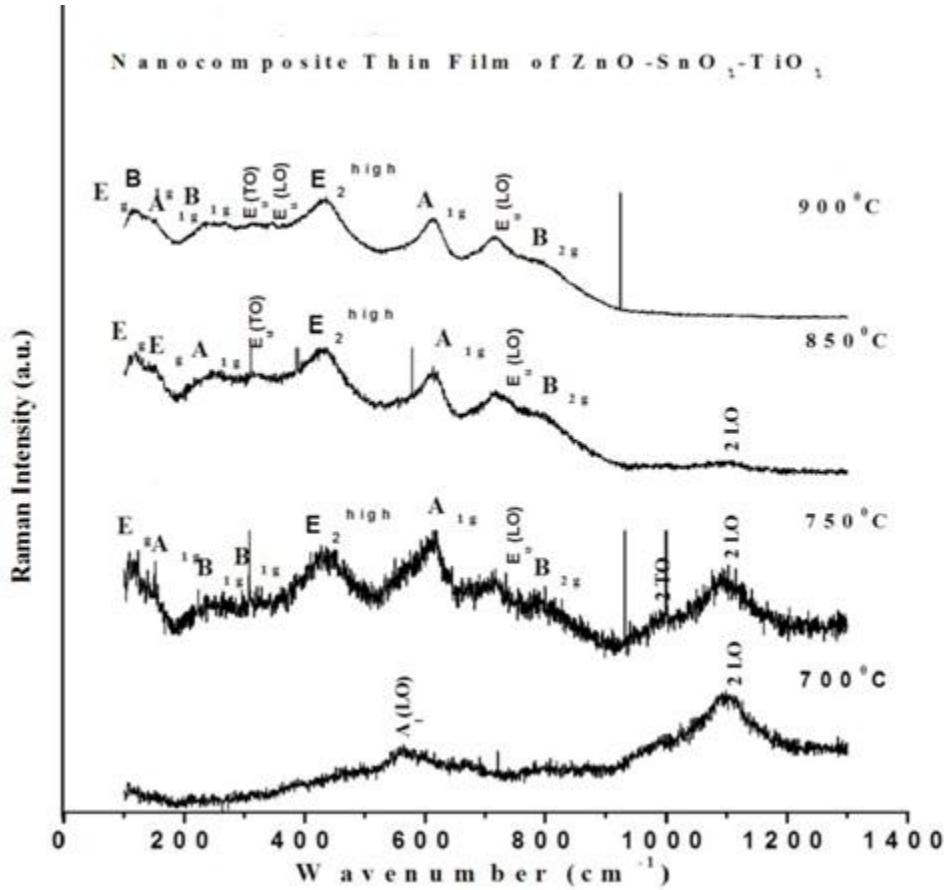


Figure 5: Raman spectra of nanocomposite ZnO-SnO₂-TiO₂ thin film annealed at 700 °C, 750 °C, 850 °C and 900 °C temperature.

As the annealing temperature increased to 850 °C, three new Raman peaks are observed at wavenumber 146 cm⁻¹, 256 cm⁻¹ and 306 cm⁻¹ which belong to vibrational mode E_g anatase TiO₂ phase, A_{1g} rutile TiO₂ and E_u(TO) tetragonal SnO₂ phase. The Raman vibrational mode E_g, E₂^{high}, A_{1g}, E_u(LO), B_{2g} and 2LO occurs at wavenumber 119 cm⁻¹, 431 cm⁻¹, 613 cm⁻¹, 716 cm⁻¹, 791 cm⁻¹ and 1102 cm⁻¹ respectively at this annealing temperature. At annealing temperature 900 °C two new Raman peaks at wave number 121 cm⁻¹ and 347 cm⁻¹ belong to vibrational mode B_{1g} and E_u(LO) tetragonal SnO₂ phase [15, 17] are occur which are not present at annealing temperature 750 °C and 850 °C. Also at this temperature Raman shifts of vibrational mode E_u(TO), A_{1g}, E_u(LO) and B_{2g} takes place and Raman peaks are found at wavenumber 310 cm⁻¹,

612 cm⁻¹, 714 cm⁻¹ and 792 cm⁻¹ respectively while in vibrational mode A_{1g} brookite TiO₂ phase and B_{1g} rutile TiO₂ phase there is found no shifting.

However, it is noticed that along with the increasing of the annealing temperature the intensity of the Raman vibrational modes reduced gradually, also the peaks are broadened as shown in fig. 5. The decreased in intensity and broadening of Raman peaks are mainly due to the presence of lattice strain and crystallite size in the grains of a nanocomposite ZnO-SnO₂-TiO₂ thin films.

3.3 UV. Vis. NIR Spectroscopy

Optical characterization of nanocomposite thin films gives more information such as optical band gap, band structure, optically active defects etc. The band gap of the nanocomposite ZnO-SnO₂-TiO₂ thin film was determined by fitting the absorption data to the direct transition:

$$\alpha hv = A(hv - E_g)^{1/2} \quad \dots (2)$$

Where α is the linear optical absorption coefficient, $h\nu$ is the photon energy, E_g is the direct band gap and A is a constant [18]. The band gap of nanocomposite ZnO-SnO₂-TiO₂ thin film was measured by plotting $(\alpha h\nu)^2$ as a function of photon energy $h\nu$, and extrapolation the linear portion of the curve to absorption equal to zero as given in fig. 6. The band gap of the nanocomposite at annealing temperature 700 °C, 750 °C, 850 °C and 900 °C are 3.68 eV, 3.70 eV, 3.74 eV and 3.76 eV respectively. The band gap slightly increases with the annealing temperature as shown in fig. 6. The inter-atomic spacing of semiconductors changes due to the strain which affects the energy band [19] and band gap increases for increase in compressive strain while decreases for increase in tensile strain [20-21]. However there are only a little bit changes in the energy band gap as strain changes of the thin film. The lowest tensile strain 0.00341 occurs at annealing temperature 750 °C which corresponds to band gap 3.70 eV while compressive strain -0.01631 occurs at annealing temperature 900 °C which corresponds to band gap 3.76 eV.

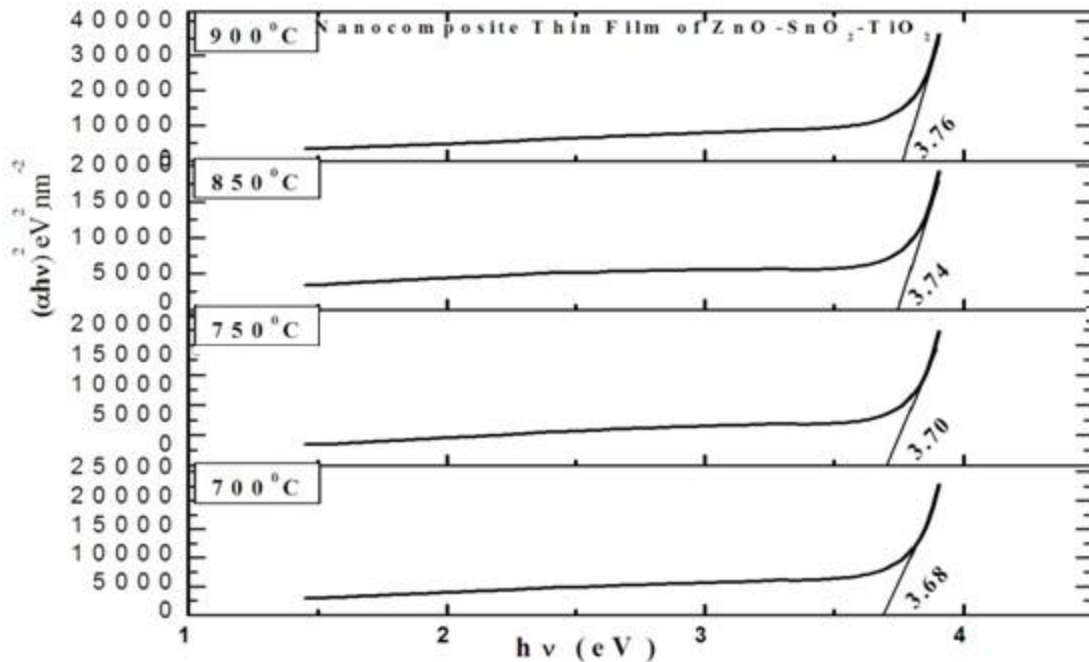


Figure 6: Plot $(\alpha h\nu)^2$ vs $h\nu$ of nanocomposite ZnO-SnO₂-TiO₂ thin film annealed at 700 °C, 750 °C, 850 °C and 900 °C.

3.4 Atomic Force Microscopy

Since the atomic force microscopic technique is powerful methods for providing the information about the surface morphology (e.g. porosity, cracks, roughness, size, and orientation of grains etc.) of as synthesized nanocomposite thin films at different annealing temperatures. The studies of thin film surface morphologies were carried out by using atomic force microscopy measurement. All thin films were scanned at several different locations on the film surface. Surface morphologies vary significantly among nanocomposite ZnO-SnO₂-TiO₂ thin films annealed at different temperatures. Fig. 7 shows AFM image from those films annealed at different temperatures but at the same initial conditions. They show the effect of annealing temperature on thin film morphology. As the annealing temperature increases particle size also increases. This increase in size of particle is due to the agglomeration of the crystallites. As the temperature increases more and more crystallite agglomeration takes place which result the increased of the size of the particle as shown in fig. 7. The shape of the particle size is nearly

spherical as revealed from the AFM images. The variation of particle size and roughness with annealing temperature are shown in table 1.

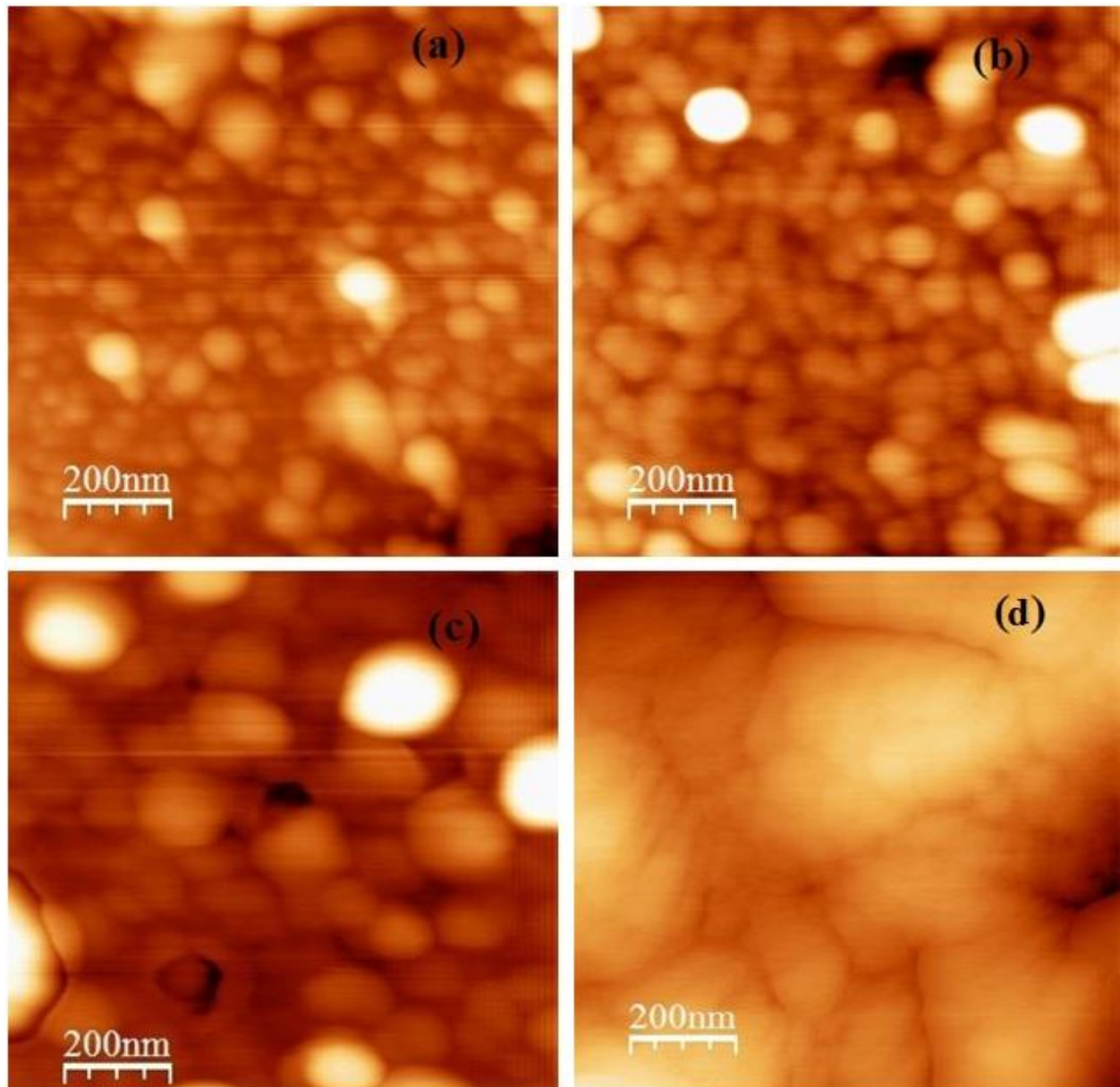


Figure 7: AFM image of nanocomposite ZnO-SnO₂-TiO₂ annealed at (a) 700 °C, (b) 750 °C, (c) 850 °C and (d) 900 °C.

4 Conclusions

Nanocomposite ZnO-SnO₂-TiO₂ thin films were prepared by spray pyrolysis method. At annealing temperature 700 °C the XRD result shows the amorphous in nature of thin film deposited on glass substrate. The crystallinity of the thin films was achieved at higher annealing temperature. The XRD spectra of thin films show the broadening of the peak which results the decrease in intensity of the XRD reflection and at high annealing temperature (900 °C) some reflection are absent which were found at low annealing temperature (750 °C). The broadening is due to the presence of non-uniform lattice strain in the nanocomposite thin films. A Raman spectrum also shows the variation of intensity of vibrational mode dependence with lattice strain and crystallite size. An XRD and Raman spectrum both confirms the formation of nanocomposite thin film. The effect of strain on the band gap of thin films are also observed but in little bit amount. The band gap decreases as tensile lattice strain increases while increases as compressive lattice strain increases. AFM image shows that as annealing temperature increases particle size also increases due to the agglomeration of the crystallite. The grains of the nanocomposite thin films are nearly spherical in shape.

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